

ABSTRACT

**Immersion Lithographic Apparatus, Drying Device,
Immersion Metrology Apparatus and Device Manufacturing Method**

An immersion lithographic apparatus is described in which a liquid removal device is arranged to remove liquid from the substrate, e.g. during exposures, through a plurality of elongate slots arranged along a line and angled to that line. The liquid removal device may act as a meniscus pinning device in an immersion hood or may be used in a drying device to remove a droplet from the substrate.

Fig 10.